

**AMENDMENT TO THE SPECIFICATION**

To correct inadvertent, typographical errors, Applicant submits the following replacement paragraph for page 10, line 7 through page 11, line 10:

The protected aluminum mass is produced by forming the unprotected aluminum mass and adding a layer forming reactant to the formed aluminum mass that preferably occurs prior to any oxidation of the surface of the aluminum mass. The layer forming reactant binds to the surface of the aluminum mass as the attached protective layer. Preferably the step of forming the unprotected aluminum mass includes processing a composition of  $\text{AlH}_3 \bullet \text{NR}_1\text{R}_2\text{R}_3$ , with  $\text{R}_1$ ,  $\text{R}_2$  and  $\text{R}_3$  independently being hydrogen or an alkyl having ~~from about 0~~ 1 to about 10 carbon atoms, that are optionally in combination with one or more heterocycles. The process results in the formation of the protected aluminum mass. In one embodiment, the process of the present invention includes a solution of known concentration of  $\text{AlH}_3 \bullet \text{NR}_3$  ( $\text{R} = \text{alkyl}$ ) in ether that is decomposed by the addition of a catalytic amount of  $\text{Ti}(\text{O}^i\text{Pr})_4$ . After the decomposition is effected and the aluminum atoms begin to nucleate, a solution of perfluoroalkyl carboxylic acid in ether is added slowly to reduce heat generation, such as dropwise. Without the use of excess complexing amine – as referenced in the Higa Patent, times of Al particle nucleation may be monitored to prevent aluminum film formation on the walls of the reaction vessel. Representative times for nucleation may include, for example without limitation, 5 minutes, 7 minutes, 10 minutes, and other such times effective for highest degree of Al particle nucleation while preventing film formation of the atomic aluminum. This allows larger Al particle sizes without film formation prior to passivation. The carboxylic acid moieties react with the aluminum surface releasing hydrogen and forming a covalent aluminum-oxygen bond thereby linking the long chain perfluoroalkyl moiety with the aluminum and coating the entire surface of the

aluminum particle with a self-assembled monolayer of perfluoroalkyl carboxylic acid moieties and preventing the nucleation (Ostwald ripening) of the Al particles.